

RECEIVED
CENTRAL FAX CENTER

MAY 23 2005

JOHN P. TAYLOR
PATENT ATTORNEY
POST OFFICE BOX 1598
TEMECULA, CA 92593-1598
(909) 303-1416 (Telephone and Fax)


FACIMILE TRANSMISSION COVER SHEET

To: Honorable Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

☒ In re application of:

Appl. No.: 10/619,978
Applicants: Yong-Bae Kim and Philippe Schoenborn
Filed: July 14, 2003
TC./A.U.: 1765
Examiner: Kin-Chan Chen
Title: PROCESS FOR REMOVAL OF PHOTORESIST MASK USED FOR MAKING VIAS
IN LOW K CARBON-DOPED SILICON OXIDE DIELECTRIC MATERIAL, AND
FOR REMOVAL OF ETCH RESIDUES FROM FORMATION OF VIAS AND
REMOVAL OF PHOTORESIST MASK
Docket No.: 01-125/1C

CERTIFICATION OF FACSIMILE TRANSMISSION	
I hereby certify that the accompanying amendment is being facsimile transmitted to the Patent and Trademark Office (Fax No. (703) 872-9308) on the date shown below;	
on	May 23, 2005
	(Date of Facsimile Transmission)
John P. Taylor, Reg. No. 22,369	
	Signature
	May 23, 2005
	Date of Signature

Total Pages (including this cover sheet): 16
Documents included:
Fax Cover Sheet 1 Pages
Amendment Transmittal Letter 2 Pages
Amendment 11 Pages
Terminal Disclaimer 2 Pages

*Missing 14 Pages*** Received: 2 pages. CH*

AMENDMENT TRANSMITTAL LETTER			ATTORNEY'S DOCKET NO. 01-125/1C
SERIAL NO. 10/619,978	FILING DATE July 14, 2003	EXAMINER Kin-Chan Chen	GROUP ART UNIT 1765
INVENTION PROCESS FOR REMOVAL OF PHOTORESIST MASK USED FOR MAKING VIAS IN LOW K CARBON-DOPED SILICON OXIDE DIELECTRIC MATERIAL, AND FOR REMOVAL OF ETCH RESIDUES FROM FORMATION OF VIAS AND REMOVAL OF PHOTORESIST			